

**PATENT NUMBER and  
ISSUE DATE**

**U.S. UTILITY Patent Application**

762  
 APPL NUM FILING DATE CLASS SUBCLASS GAU EXAMINER  
 10054962 01/25/2002 438 692 1765 *Wic-hen, K*

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**\*\*CONTINUING DATA VERIFIED:**

**\*\* FOREIGN APPLICATIONS VERIFIED:**

PG-PUB	DO NOT PUBLISH <input type="checkbox"/>	RESCIND <input type="checkbox"/>	
Foreign priority claimed 35 USC 119 conditions met		<input type="checkbox"/> yes <input type="checkbox"/> no <input type="checkbox"/> yes <input type="checkbox"/> no	ATTORNEY DOCKET NO
Verified and Acknowledged Examiner's initials			4006-150
TITLE : Method for controlling and monitoring a chemical mechanical polishing process			
U.S. DEPT. OF COMM./PAT. & TM-PTO-436L (Rev. 12-94)			

<b>NOTICE OF ALLOWANCE MAILED</b>		<b>CLAIMS ALLOWED</b>	
		<b>Assistant Examiner</b>	<b>Total Claims</b> _____ <b>Print Claim for O.G.</b> _____
<b>ISSUE FEE</b>		<b>DRAWING</b> Sheets Drawg. _____ Figs. Drawg. _____ Print Fig. _____	
<b>Amount Due</b>	<b>Date Paid</b>		
		<b>Primary Examiner</b>	
		<b>PREPARED F R ISSUE</b>	
		<b>Applicant Examiner</b>	
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